

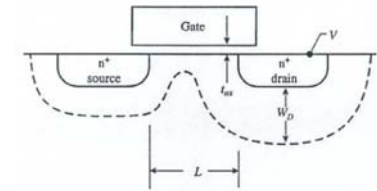
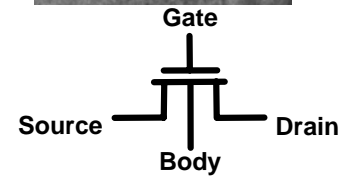
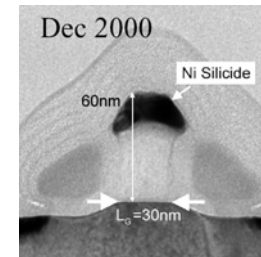
# MOS Transistor

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## MOS Transistor



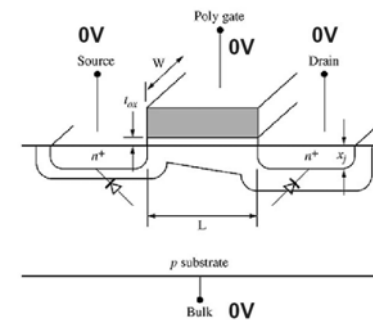
Kuroda, IEDM panel

2

## MOS Transistor Current Equation



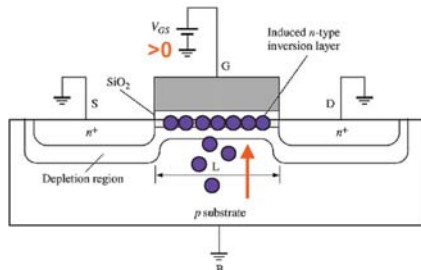
## Basic Operation (1)



- Device is in cut-off region
- Simply, two back-to-back reverse biased pn diodes.

4

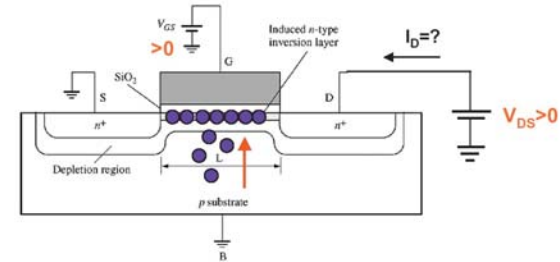
## Basic Operation (2)



- With a positive gate bias, electrons are pulled toward the positive gate electrode
- Given a large enough bias, the electrons start to “invert” the surface (p→n type), a conductive channel forms
- Threshold voltage  $V_t$

5

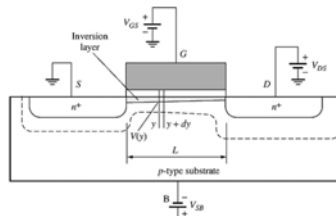
## Basic Operation (3)



- Current flows from drain to source with a positive drain voltage
- What is current in terms of  $V_{gs}$ ,  $V_{ds}$ ,  $V_{bs}$ ?

6

## MOS Current



$$I_{ds} = 0$$

$$V_{gs} < V_t \quad : \text{cut-off}$$

$$I_{ds} = \mu_e C_{ox} W/L ((V_{gs} - V_t) V_{ds} - 0.5 V_{ds}^2)$$

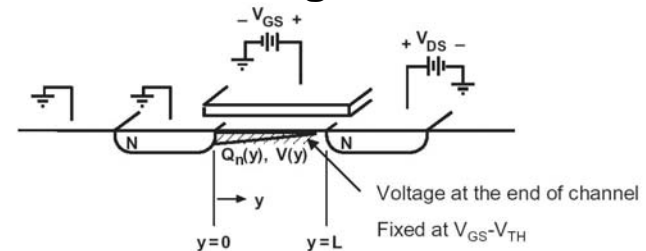
$$0 < V_{ds} < V_{gs} - V_t \quad : \text{triode (linear) mode}$$

$$I_{ds} = \mu_e C_{ox} W/(2L) (V_{gs} - V_t)^2$$

$$0 < V_{gs} - V_t < V_{ds} \quad : \text{saturation mode}$$

7

## Channel Length Modulation

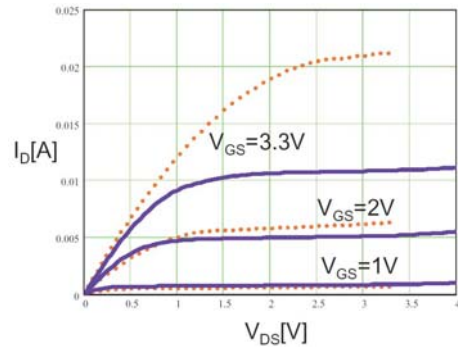


- Pinch-off depletion layer width increases as the drain voltage increases
- Extreme case of this is punch-through

$$L = L_o - \zeta V_{ds} \quad I_{ds} = I_{dsat} \times \frac{L_o}{L_o - \zeta V_{ds}} = I_{dsat} \times (1 + \lambda V_{ds})$$

8

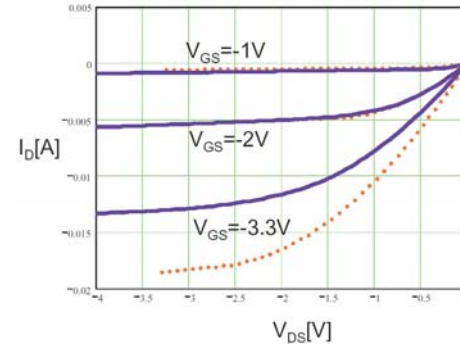
## Simulation versus Model (NMOS)



- The square-law model doesn't match well with simulations
- Only fits for low  $V_{GS}$ , low  $V_{DS}$  (low E-field) conditions

9

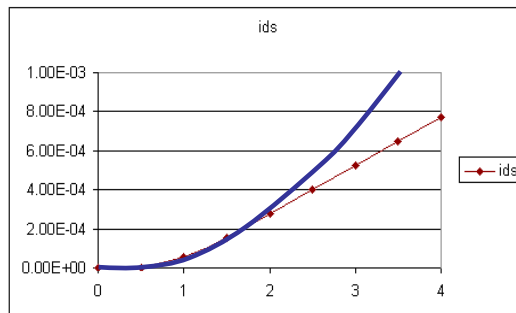
## Simulation versus Model (PMOS)



- Not as bad as the NMOS device
- Still large discrepancies at high E-field conditions

10

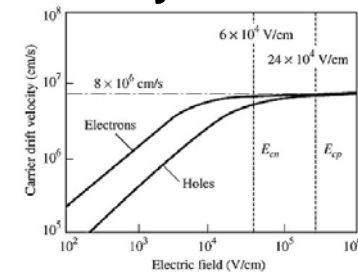
## Simulation versus Model ( $I_{ds}$ vs. $V_{gs}$ )



- Saturation current does not increase quadratically
- The simulated curves look like a straight line
- Main reason for discrepancy: velocity saturation

11

## Velocity Saturation



- E-fields have gone up as dimensions scale
- Unfortunately, carrier velocity in silicon is limited
- Electron velocity saturates at a lower E-field than holes
- Mobility ( $\mu_e = v/E$ ) degrades at higher E-fields
- Simple piecewise linear model can be used

12

## Velocity Saturation

$$v = \frac{\mu_e E}{\left(1 + \left(\frac{E}{E_c}\right)^n\right)^{1/n}} \quad \text{for } E < E_c \quad E_c = \frac{2v_{sat}}{\mu_e}$$

$$= v_{sat} \quad \text{for } E > E_c$$

[Toh, Ko, Meyer, JSSC, 8/1988]

- Modeled through a variable mobility
- $n=1$  for PMOS,  $n=2$  for NMOS
- To get an analytical expression, let's assume  $n=1$

13

## Velocity Saturation

- Plug it into the original current equation

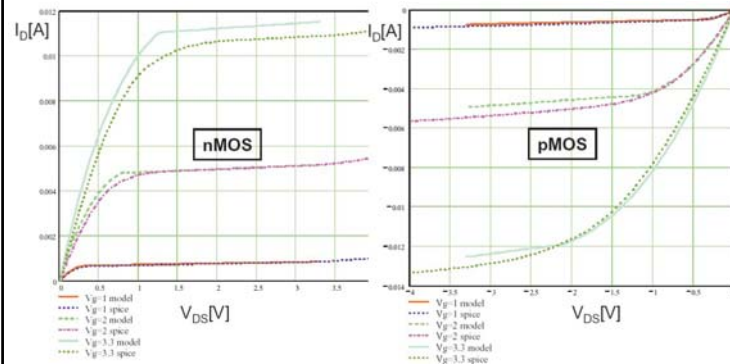
$$\therefore I_{ds} = \begin{cases} \mu_e C_{ox} \frac{W}{L} \left( (V_{gs} - V_t) V_{ds} - \frac{V_{ds}^2}{2} \right) \times \frac{1}{1 + \frac{V_{ds}}{E_c L}} & (V_{ds} < V_{dsat}) \\ C_{ox} W v_{sat} (V_{gs} - V_t - V_{dsat}) & (V_{ds} > V_{dsat}) \end{cases}$$

Equate the two expressions to get

$$V_{dsat} = \frac{(V_{gs} - V_t) E_c L}{(V_{gs} - V_t) + E_c L}$$

14

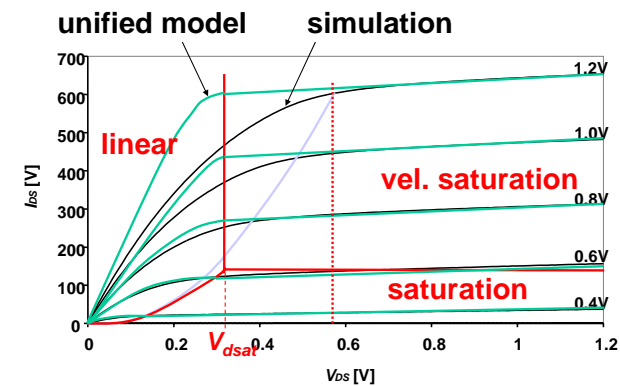
## Simulation versus Model



- Model incorporating velocity saturation matches fairly well with simulation

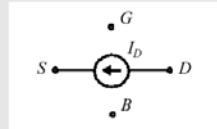
15

## Unified MOS Model



16

## Unified MOS Model Equations



$$I_D = 0 \text{ for } V_{GT} \leq 0$$

$$I_D = k' \frac{W}{L} \left( V_{GT} V_{min} - \frac{V_{min}^2}{2} \right) (1 + \lambda V_{DS}) \text{ for } V_{GT} \geq 0$$

$$\text{with } V_{min} = \min(V_{GT}, V_{DS}, V_{DSAT}),$$

$$V_{GT} = V_{GS} - V_T,$$

$$\text{and } V_T = V_{T0} + \gamma (\sqrt{-2\phi_F + V_{SB}} - \sqrt{-2\phi_F})$$

$\gamma$  - body effect parameter

- Model presented is compact and suitable for hand analysis.
- Still have to keep in mind the main approximation: that  $V_{DSat}$  is constant.
- But the model still works fairly well.

17

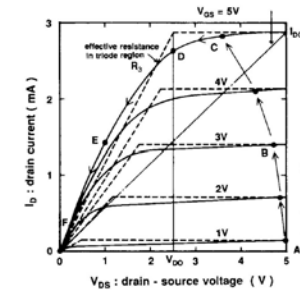
## Alpha Power Law

- Simple empirical model for short channel MOS

$$I_{ds} = \frac{W}{2L} \mu_e C_{ox} (V_{gs} - V_t)^\alpha$$

[Sakurai and Newton, JSSC 1990]

- Parameter  $\alpha$  is between 1 and 2
- $\alpha=1-1.2$  for short channel devices
- Parameters  $\alpha$  and  $V_t$  are fitted to measured data for minimum square error  $\rightarrow$  fitted  $V_t$  can be different from physical  $V_t$



18